

补充材料：二维 WTe₂晶格对称性的光学研究*

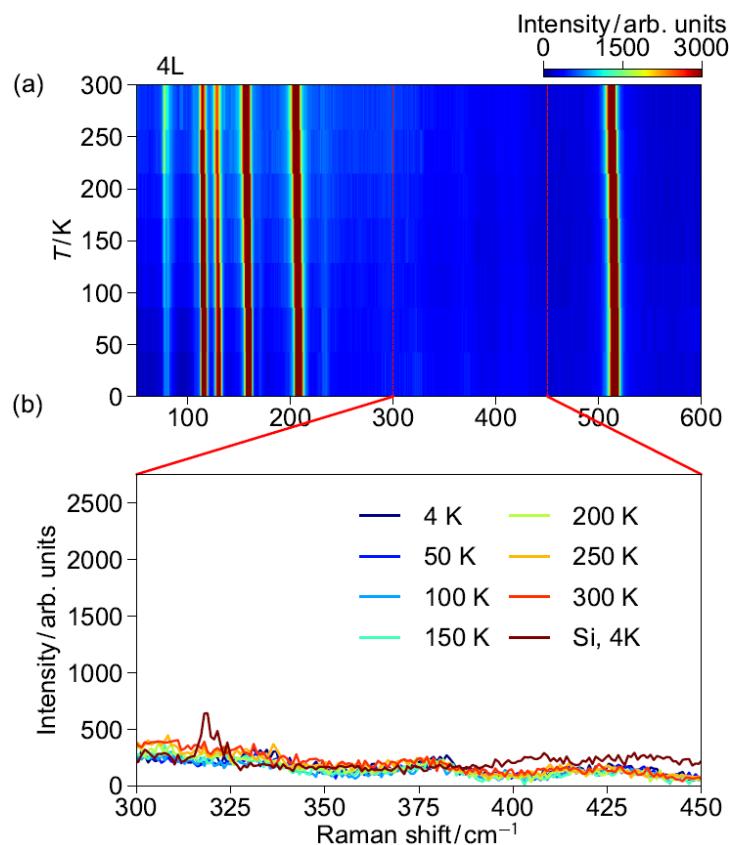
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图S1. (a)四层WTe₂在平行偏振条件下的温度依赖拉曼散射强度图; (b)为(a)中 300 — 450 cm⁻¹范围内在若干温度点的拉曼谱. 激发波长为532 nm. 衬底为SiO₂/Si

Fig. S1. (a) Temperature dependent Raman scattering intensity map for tetralayer WTe₂ on SiO₂/Si, measured in the parallel polarization configuration. (b) The corresponding spectra between 300 and 450 cm⁻¹ at selected temperatures. Excitation wavelength of 532 nm was used.

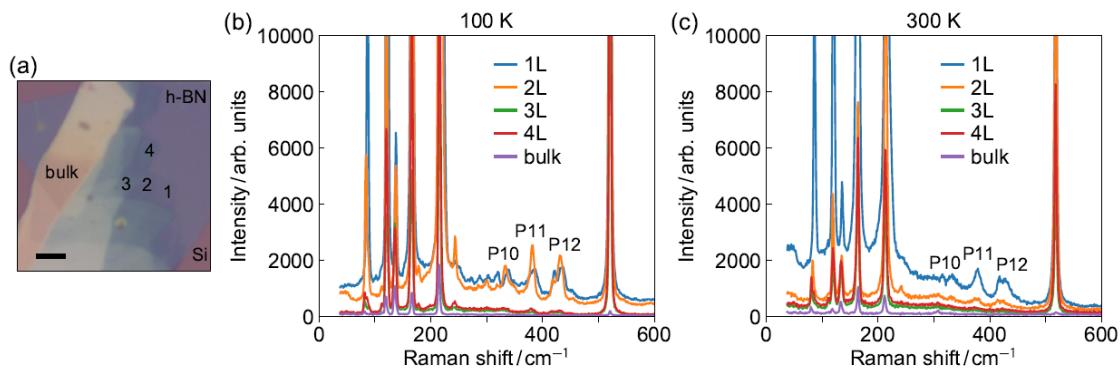


图 S2. (a) 机械剥离制备的 WTe₂ 样品的光学照片. 薄层样品的厚度用数字标出. 衬底为 SiO₂/Si, 其中氧化层厚度为 300 nm. 比例尺: 5 μm. (b), (c) 1—4 层和块体 WTe₂ 在平行偏振条件下 100 K 和 300 K 的拉曼谱. 激发波长为 532 nm. 入射功率为 0.2 mW

Fig. S2. (a) Optical image of mechanically exfoliated WTe₂, with layer numbers marked for the thin regions. The substrate is SiO₂/Si with a 300 nm oxide layer. Scale bar: 5 μm. (b), (c) Raman spectra of monolayer, bilayer, trilayer, tetrалayer, and bulk WTe₂ at 100 K and 300 K, measured in the parallel polarization configuration with 532 nm excitation and an incident power of 0.2 mW.

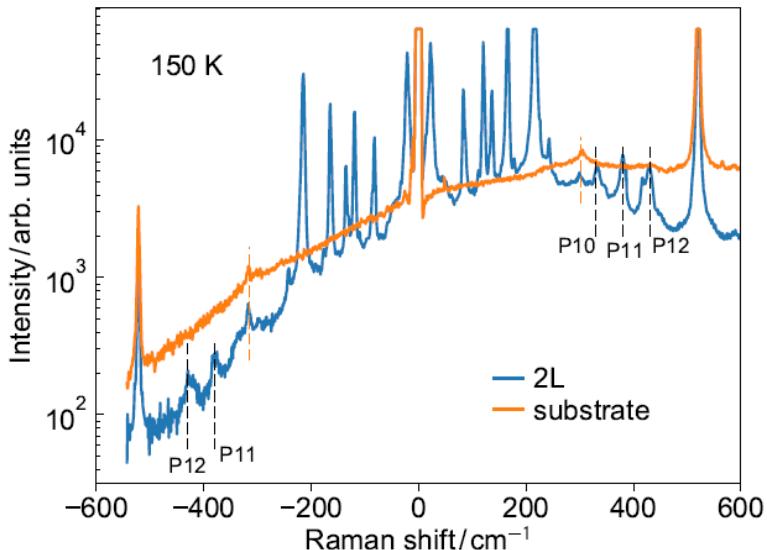
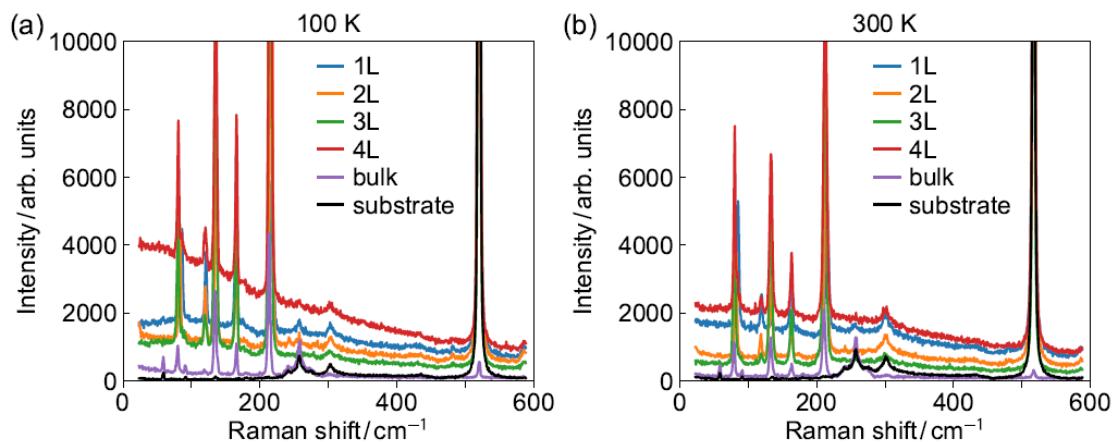


图 S3. 双层 WTe₂ 在平行偏振条件下的拉曼谱. 激发波长为 532 nm. 该测量采用了较大的入射功率(0.6 mW), 以确保获得 300—450 cm⁻¹ 范围的反斯托克斯信号

Fig. S3. Raman spectra of bilayer WTe₂, measured in the parallel polarization configuration with 532 nm excitation. A large incident power of 0.6 mW was used to ensure the observation of anti-Stokes lines in the range of 300—450 cm⁻¹.



图S4. 与补充图2中相同的1—4层和块体WTe₂样品在633 nm激发波长、平行偏振条件下100 K和300 K的拉曼谱。入射功率为0.2 mW

Fig. S4. Raman spectra of monolayer, bilayer, trilayer, tetralayer, and bulk WTe₂ used in Supplementary Fig. 2, measured at 100 K and 300 K in the parallel polarization configuration with 633 nm excitation and an incident power of 0.2 mW.